



## Supporting Information

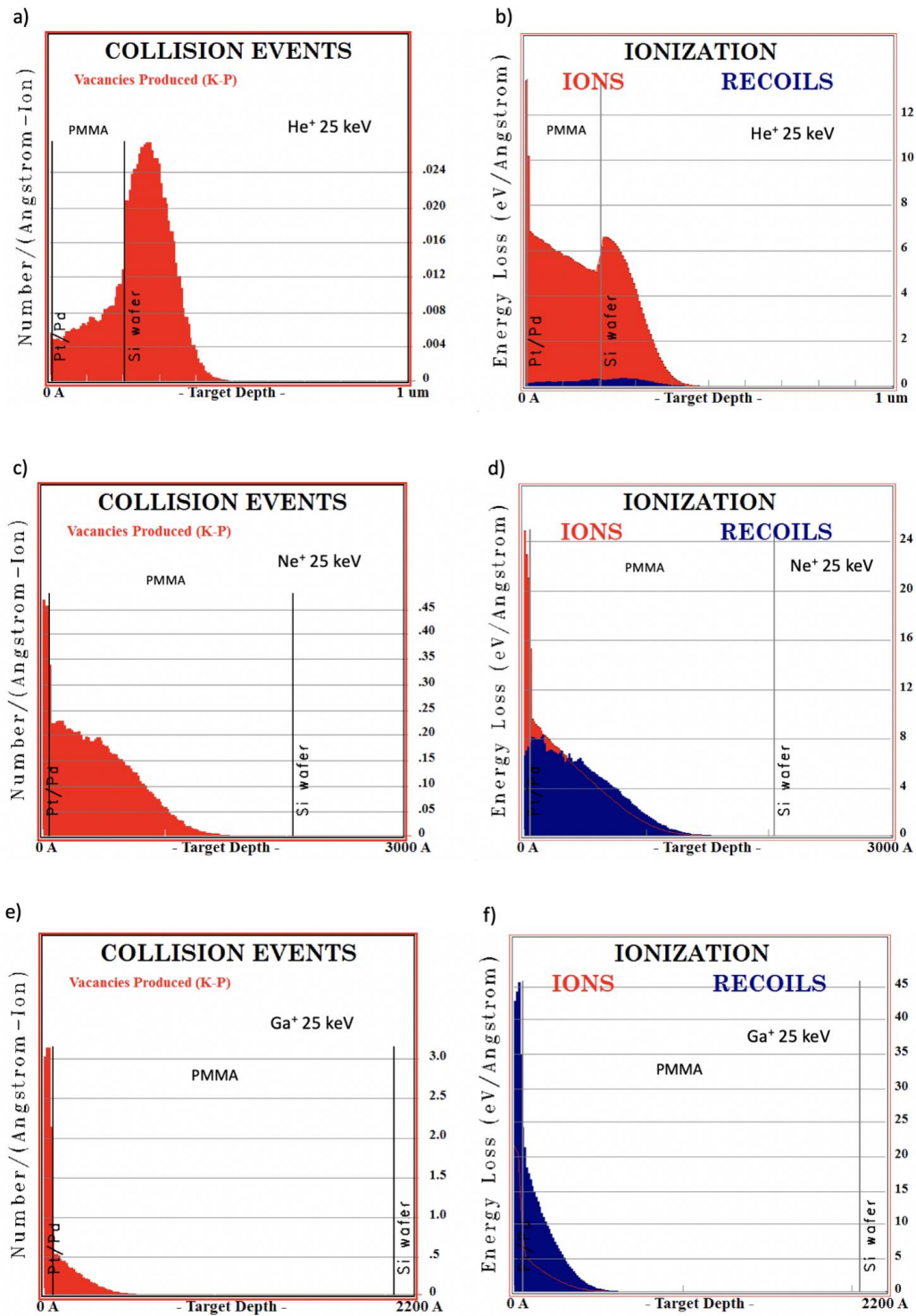
for

### **Out-of-plane surface patterning by subsurface processing of polymer substrates with focused ion beams**

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### **SRIM simulations**



**Figure S1:** SRIM simulations of collision and ionization in the 5 nm Pt<sub>60</sub>Pd<sub>40</sub>/200 nm PMMA samples, irradiated with (a, b) He<sup>+</sup>, (c, d) Ne<sup>+</sup>, and (e, f) Ga<sup>+</sup> FIBs.